

IN THE CLAIMS

1-22 (Cancelled)

1 23. (Original) A lithographic tool for patterning a substrate, comprising:
2 a spatial light modulator, said spatial light modulator comprising at least one area
3 array of individually switchable elements;
4 a light source configured to illuminate said spatial light modulator;
5 imaging optics configured to project a blurred image of said spatial light modulator
6 on said substrate; and
7 an image movement mechanism for moving said image across the surface of said
8 substrate.

1 24. (Original) A lithographic tool as in claim 23, wherein said spatial light modulator
2 comprises at least one digital micro-mirror device.

1 25. (Original) A lithographic tool as in claim 23, wherein said light source is a
2 continuous light source.

1 26. (Original) A lithographic tool as in claim 23, wherein said light source is an arc
2 lamp.

1 27. (Original) A lithographic tool as in claim 23, wherein said light source is a laser.

1 28. (Original) A lithographic tool as in claim 27, wherein said laser is a continuous
2 laser.

1 29. (Original) A lithographic tool as in claim 27, wherein said laser is a quasi-
2 continuous laser.

1 30. (Original) A lithographic tool as in claim 23, wherein said imaging optics is a
2 telecentric projection lens system.

1 31. (Original) A lithographic tool as in claim 23, wherein said imaging optics is
2 configured to form a defocused image of said spatial light modulator.

1 32. (Original) A lithographic tool as in claim 23, wherein said imaging optics
2 comprises a diffuser configured to blur said image of said spatial light modulator.

1 33. (Original) A lithographic tool as in claim 23, wherein said imaging optics has a
2 numerical aperture adjusted such that said image of said spatial light modulator is blurred.

1 34. (Original) A lithographic tool as in claim 23, wherein said imaging optics
2 comprises a microlens array configured to blur said image of said spatial light modulator.

1 35. (Original) A lithographic tool as in claim 23, wherein said imaging optics
2 comprises a single projection lens system.

1 36. (Original) A lithographic tool as in claim 23, wherein said imaging optics
2 comprises a projection lens system for each said area array.

1 37. (Original) A lithographic tool as in claim 23, wherein said image movement
2 mechanism comprises a stage on which said substrate is carried.

1 38. (Original) A lithographic tool as in claim 23, wherein said image movement
2 mechanism comprises a stage on which said spatial light modulator is carried.

1 39. (Original) A lithographic tool as in claim 38, wherein said imaging optics is carried
2 on said stage.

1 40. (Original) A lithographic tool as in claim 23, wherein said image movement
2 mechanism comprises rotatable, spaced apart, axially parallel film drums, said substrate
3 being wrapped around and tensioned between said drums.

1 41. (Original) A lithographic tool as in claim 23, further comprising a control
2 computer configured to control switching said elements of said spatial light modulator
3 while said image is moving across the surface of said substrate.

1 42. (Original) A lithographic tool as in claim 23, further comprising a substrate height
2 measuring system.

1 43. (Original) A lithographic tool for patterning a substrate, comprising:
2 a spatial light modulator, said spatial light modulator comprising a multiplicity of
3 area arrays of individually switchable elements;
4 a light source configured to illuminate said spatial light modulator;
5 a multiplicity of projection lens systems configured to project a blurred image of

6 said spatial light modulator on said substrate; and
7 an image movement mechanism for moving said image across the surface of said
8 substrate;
9 wherein the number of said area arrays is greater than the number of said
10 projection lens systems.

1 44. (Original) A lithographic tool as in claim 43, wherein said number of projection
2 lens systems is a submultiple of said number of area arrays.

45-62. (Cancelled)

1 63. (Original) A lithographic tool for patterning a substrate, comprising:
2 a spatial light modulator, said spatial light modulator comprising at least one area
3 array of individually switchable elements;
4 a light source configured to illuminate said spatial light modulator;
5 imaging optics configured to project a blurred image of said spatial light modulator
6 on said substrate;
7 a light switching mechanism positioned on a light path, said light path going from
8 said light source to said spatial light modulator and ending at said substrate, said light
9 switching mechanism being configured to control passage of light along said light path;
10 and
11 an image movement mechanism for moving said image across the surface of said
12 substrate.

1 64. (Original) A lithographic tool as in claim 63, wherein said light switching

2 mechanism is a second spatial light modulator.

1 65. (Original) A lithographic tool as in claim 63, wherein said light switching
2 mechanism is a shutter.

1 66. (Original) A lithographic tool as in claim 63, wherein said light switching
2 mechanism is integrated with said light source.

1 67. (Original) A lithographic tool for patterning a substrate, comprising:
2 a first spatial light modulator, said first spatial light modulator comprising at least
3 one area array of individually switchable elements;
4 a light source configured to illuminate said first spatial light modulator;
5 imaging optics configured to project an image of said first spatial light modulator
6 on said substrate;
7 a second spatial light modulator positioned on a light path, said light path going
8 from said light source to said first spatial light modulator and ending at said substrate, said
9 second spatial light modulator being configured to control passage of light along said light
10 path; and
11 an image movement mechanism for moving said image across the surface of said
12 substrate.

1 68. (Original) A lithographic tool for patterning a substrate, comprising:
2 a spatial light modulator, said spatial light modulator comprising at least two area
3 arrays of individually switchable elements;
4 a light source configured to illuminate said area arrays;

5 imaging optics configured to project images of said area arrays on said substrate, at
6 least two of said images of said area arrays overlapping in register; and
7 an image movement mechanism for moving said images across the surface of said
8 substrate.

69-79. (Cancelled)